Fully-automatic BG Tape remover for single wafer.

After the wafer is aligned, the back grinding tape is UV irradiated as necessary. Then the peeling tape is attached to the wafer periphery by heat seal method, and back grinding tape removal is performed.

By using our unique wafer holding table and the new peeling method that reduces stress on the wafer, back grinding tape removal is performed without any contact with the wafer backside.

By adopting the non-contact wafer backside handling method, contamination of wafer is prevented.

Outline

- Fully-automatic BG Tape remover for single wafer.
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Facility

<table>
<thead>
<tr>
<th>Power Supply</th>
<th>Voltage</th>
<th>AC200-230V ±10% (AC190-253V)</th>
</tr>
</thead>
<tbody>
<tr>
<td>Frequency</td>
<td>50/60Hz</td>
<td></td>
</tr>
<tr>
<td>Phase</td>
<td>single phase</td>
<td></td>
</tr>
<tr>
<td>Power consumption</td>
<td>3.5kW (with UV Irradiation System: 10kW)</td>
<td></td>
</tr>
</tbody>
</table>

<table>
<thead>
<tr>
<th>Air Supply</th>
<th>Air pressure</th>
<th>0.6-0.8MPa</th>
</tr>
</thead>
<tbody>
<tr>
<td>Air consumption</td>
<td>&gt;200L/min (ANR)</td>
<td></td>
</tr>
</tbody>
</table>

<table>
<thead>
<tr>
<th>Vacuum Supply</th>
<th>Vacuum pressure</th>
<th>&gt;-80kPa</th>
</tr>
</thead>
</table>

Applicable Wafer Size

300mm

Please inquire about options for compatibility with specific wafer sizes.

Size

| Width | 1,440mm |
| Depth | 2,105mm |
| Height | 1,800mm |

(excluding the signal tower and protruding parts)

Weight

1,600kg

UPH

45wafers/hour

The above processing capacity is based on following conditions:

Wafer : 300mm diameter non-polished mirror wafer
Back grinding tape : E-6142S from LINTEC

Option

- Host Communication Function (Communication Format: Conforms to SECS-I and HSMS/Software: Conforms to GEM)
- Compatible with clean room applications, and suitable for front-end process

Suitable Tapes

- BG Tape: Adwill E series, P series

External View

[Image of the machine with dimensions and views]

Unit:mm

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